

**Collaboration to Bring Nanoimprint Lithography to Mainstream Manufacturing – September 27, 2022**

ST. FLORIAN, Austria, Sept. 27, 2022 — EV Group (EVG) — a provider of wafer bonding and lithography equipment for the MEMS, nanotechnology, and semiconductor markets — and photomask provider Toppan Photomask Co. Ltd. entered into an agreement to jointly market nanoimprint lithography (NIL) as a high-volume manufacturing process for the photonics industry. Together, the companies will provide NIL development kits that include master templates from Toppan Photomask and equipment and process development services provided by EVG.



*Process engineers examine a 200-mm wafer with metalenses replicated using a master manufactured by Toppan Photomask and a nanoimprint lithography process from EVG. The companies are collaborating to establish the process as an industry standard for photonics manufacturing. Courtesy of EV Group.*

The collaboration aims to establish NIL as an industry standard production process for photonics manufacturing. EVG will offer NIL technology and product demonstrations at the NILPhotonics Competence Center at its headquarters in Austria.

[https://www.photonics.com/Articles/Collaboration\\_to\\_Bring\\_Nanoimprint\\_Lithography\\_to/a68392](https://www.photonics.com/Articles/Collaboration_to_Bring_Nanoimprint_Lithography_to/a68392)